

PTO-1449		<div style="border: 1px solid black; border-radius: 50%; padding: 5px; display: inline-block;"> OIFE MAY 11 2006 Filing Date </div>		Attorney's Docket Number RD27416-2	Serial Number 10/638,099	
INFORMATION DISCLOSURE STATEMENT BY APPLICANT LIST OF ITEMS (Use several sheets if necessary)				Name of Applicant Gallucci et al.		
				Filing Date 08/07/2003	Group Art 1711	
U.S. PATENT DOCUMENTS						
Examiner Initial	Document Number	Date	NAME	Class	Subclass	Filing Date If Appropriate
tt	4754128	6/28/1988	Takeda et al.			/
	4942073	6/17/1990	Era et al.			
	5118573	6/2/1992	Tawara et al.			
	5297132	3/22/1994	Takano et al.			
	5330852	7/19/1994	Gerstenberg et al.			
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✓	6183829	2/6/2001	Daecher et al.			
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tt	2002/0025443	2/28/2002	Ohno			
FOREIGN PATENT DOCUMENTS						
Examiner Initial	Document Number	Date	COUNTRY	Class	Subclass	TRANSLATION YES NO
tt	2099852	07-1993	Canada			X
OTHER INFORMATION (including author, title, date, pertinent)						
tt	Y.Barrell et al., "Expanding Thermal Plasma for Fast Deposition of Scratch-Resistant SiC _x HyO _z Films", Surface and Coatings Technology 180-181 (2004) 367-371					
	M.F.A.M. van Hest doctoral thesis, "High Rate Deposition of Silicone Oxide Like Films" pages 95-108, 133-154, 167-169 (2002)					
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✓	JP63-201929; 08-1988; Abstract Only (2 pages)					
EXAMINER <i>Thao Tran</i>				DATE CONSIDERED <i>6/20/06</i>		
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